

Rapid characterization of SiPMs for nEXO and future noble liquid experiments

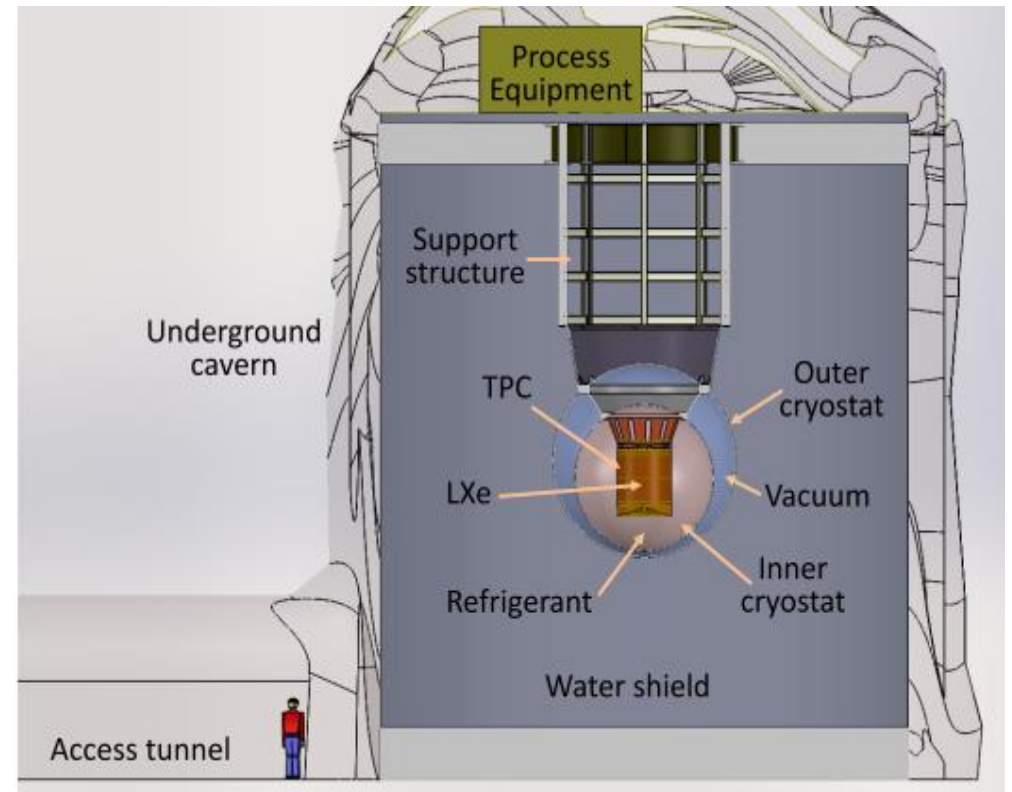


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Enriched Xenon Observatory (nEXO)

- nEXO is a single-phase 5-tonne scale Liquid Xenon (LXe) experiment to be located in the SNOLAB cryopit .
- Looking for hypothetical neutrinoless double beta decay in an isotope Xe^{136} .
$$Xe^{136} \rightarrow Ba^{136} + 2e^{-}$$
- nEXO targets to achieve the half-life sensitivity of $\sim 10^{28}$ years and for that, at least 1% detector energy resolution is required at the Q-value ($Q_{\beta\beta} = 2.458$ MeV) of the decay.

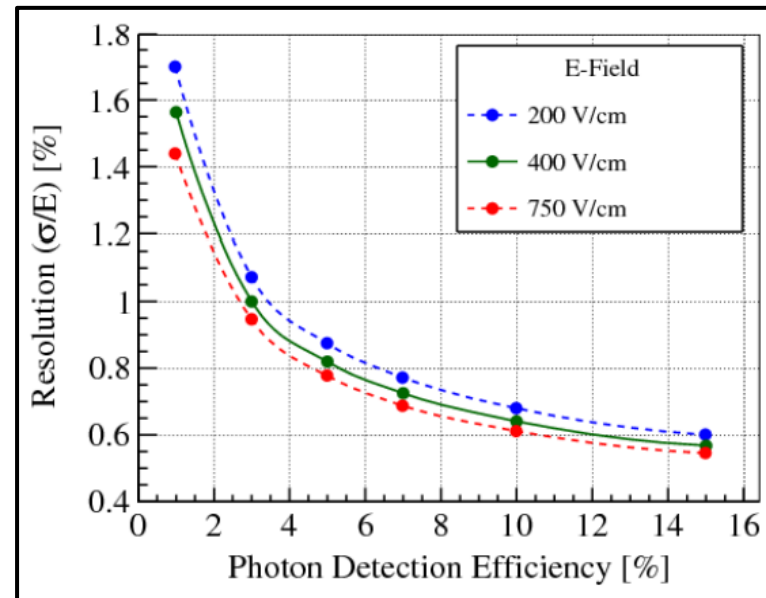


**Design of nEXO experiment
(arXiv:1805.11142)**

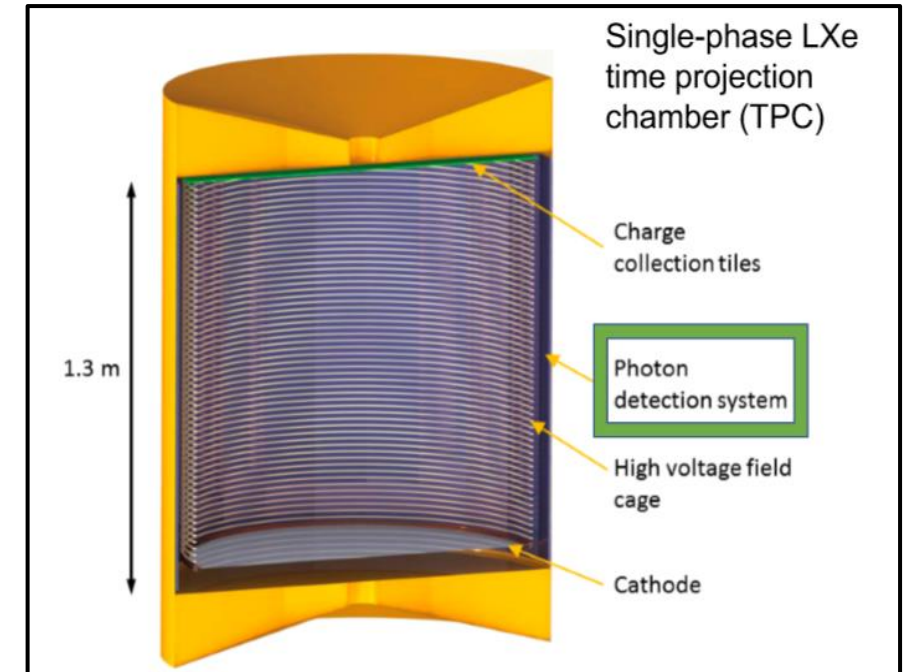
nEXO light detection system

nEXO plans to install vacuum ultraviolet silicon photomultipliers (VUV-SiPMs) to detect xenon scintillation photons (175nm).

- Detector energy resolution relies significantly on the efficiency of scintillation light detection.
- Important to characterize the parameters and performance of SiPM before their operation in the experiment.



Energy resolution as a function of the light detection efficiency for three different drift electric fields.



Sketch of the planned nEXO TPC;
arXiv:1805.11142

Motivation

- Silicon photomultipliers (SiPMs) are emerging technology in photon detection in particle physics.
- Large future experiments like **nEXO**, **ARGO** etc. will use SiPM based light detection system



SiPM tile

Challenges

- Quality control and testing of these large number of SiPMs will be a challenge.
- A quick and reliable SiPM testing technique is required at all stages (from single SiPM to fully installed system).

Goals of this project

Current-voltage (IV) characterization of SiPM

Develop the IV fit model to understand the IV curves

Use fit model to extract the empirical parameters of SiPMs

Compare and verify the results from IV analysis with pulse analysis

Extend the study to different SiPM devices at a range of temperatures in different light conditions

VERA* setup at TRIUMF

SiPM devices

- FBK** VUV HD3
- Hamamatsu VUV4

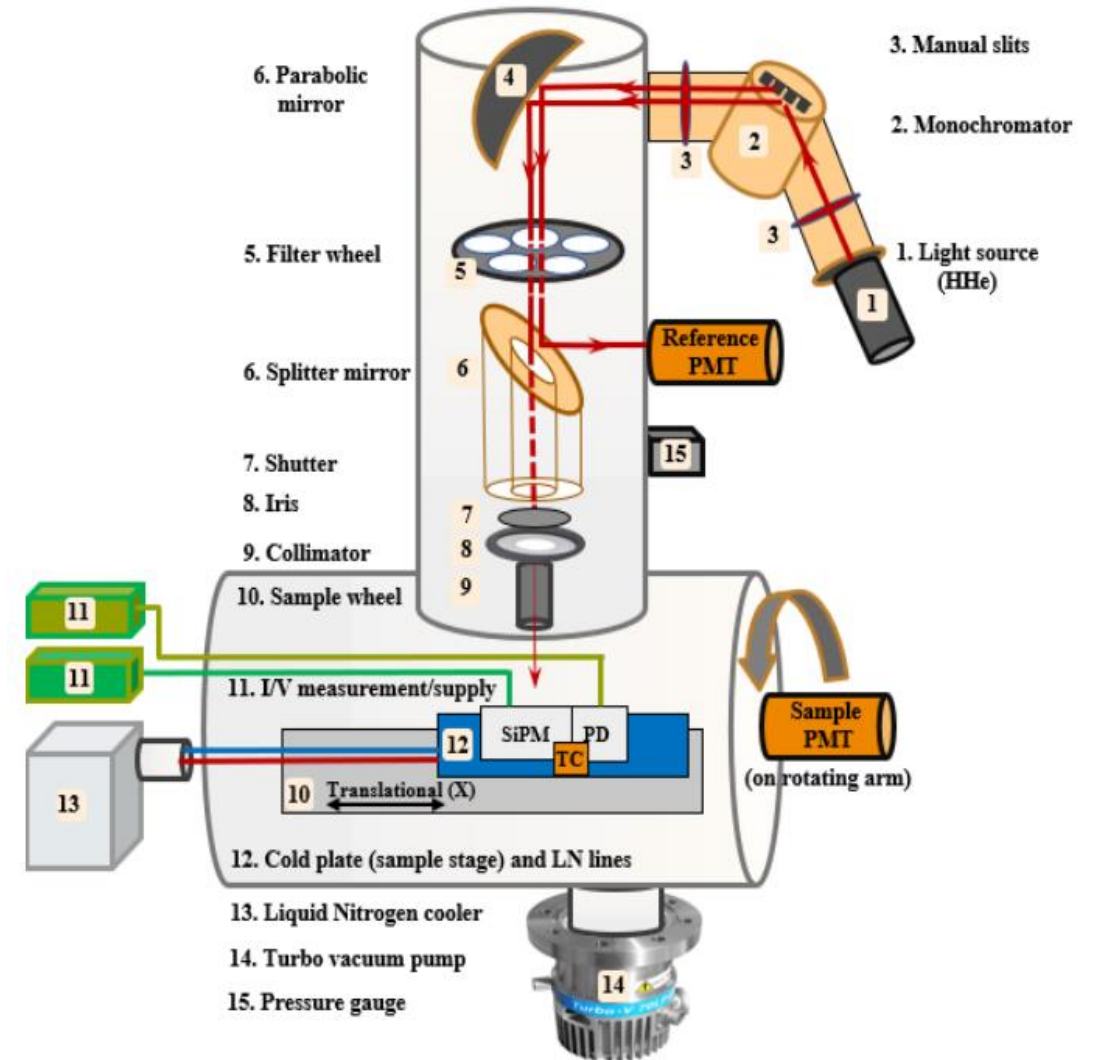
Temperature range

- -110° C to +20° C

Light conditions

- Dark
- Light source – 175nm & 385nm

Thanks to Dr. Fabrice Retiere and Dr. Mahsa Mahtab (TRIUMF) for their support in this project



VERA setup at TRIUMF used to take measurements for SiPMs

*VERA – Vacuum Emission, Reflectance and Absorbance

** FBK - Fondazione Bruno Kessler

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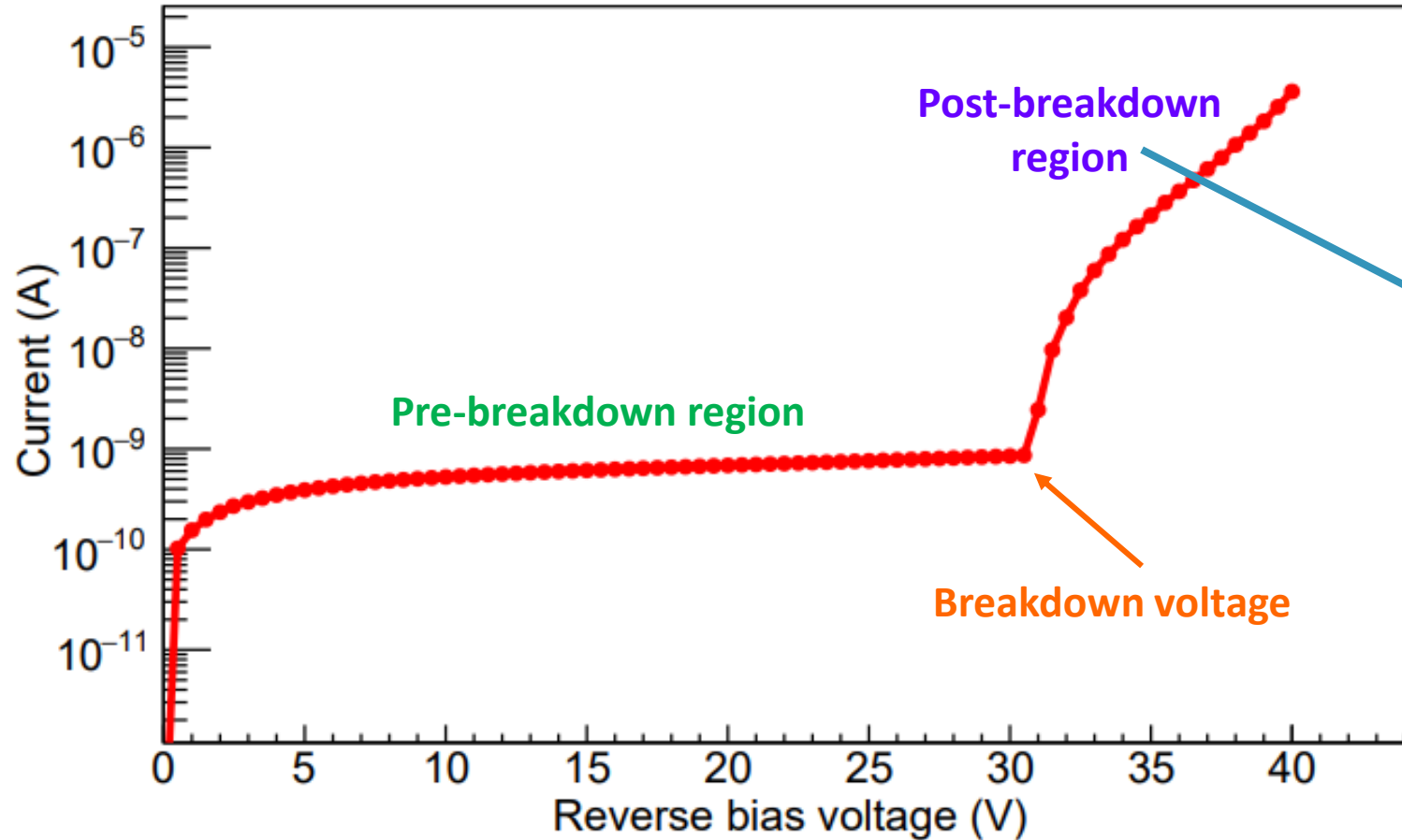


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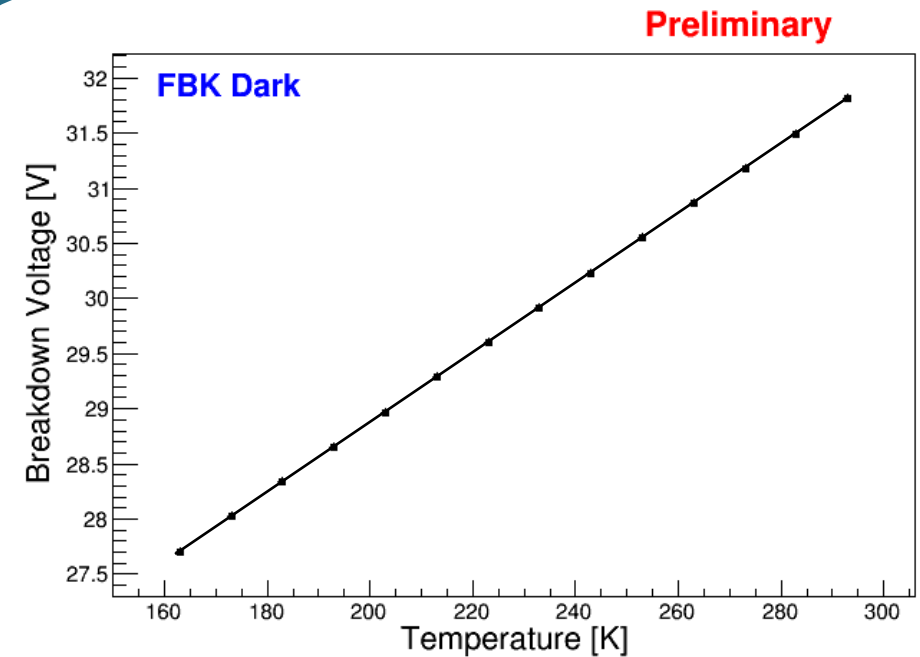
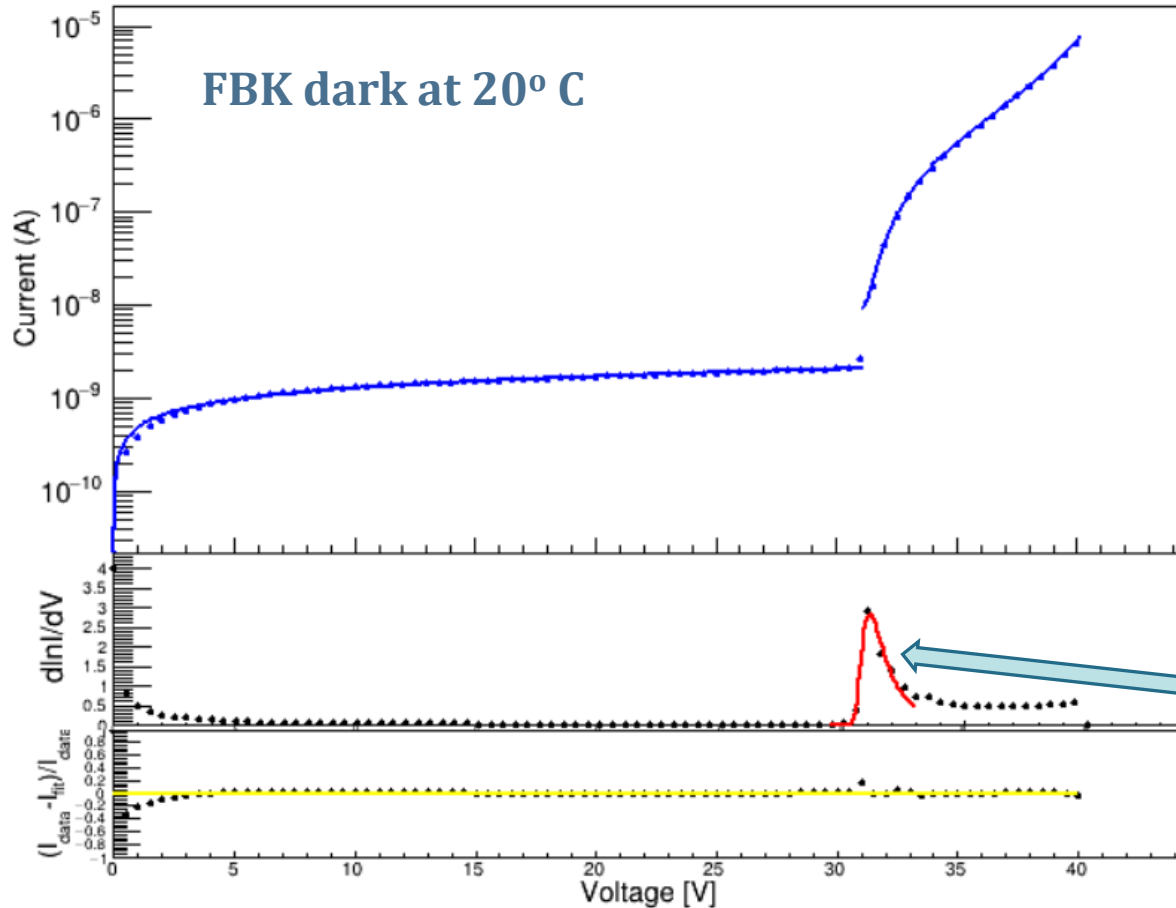
SiPM IV curve



Post-breakdown region

- SiPMs are usually operated in post breakdown region
- Geiger mode – a single charge carrier is able to trigger an avalanche
- High gain
- Correlated avalanche noise

Breakdown voltage

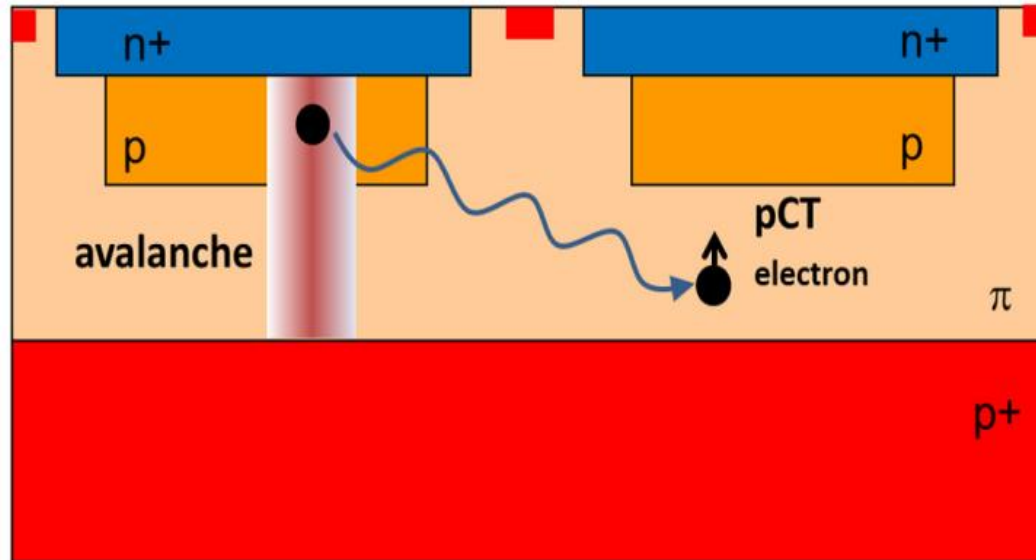


Breakdown voltage increases linearly with temperature.

- Relative logarithmic derivation method to extract the breakdown voltage.
- **Landau fit function** on $\frac{d(\ln(I))}{dV}$ and mean value gives the breakdown voltage.

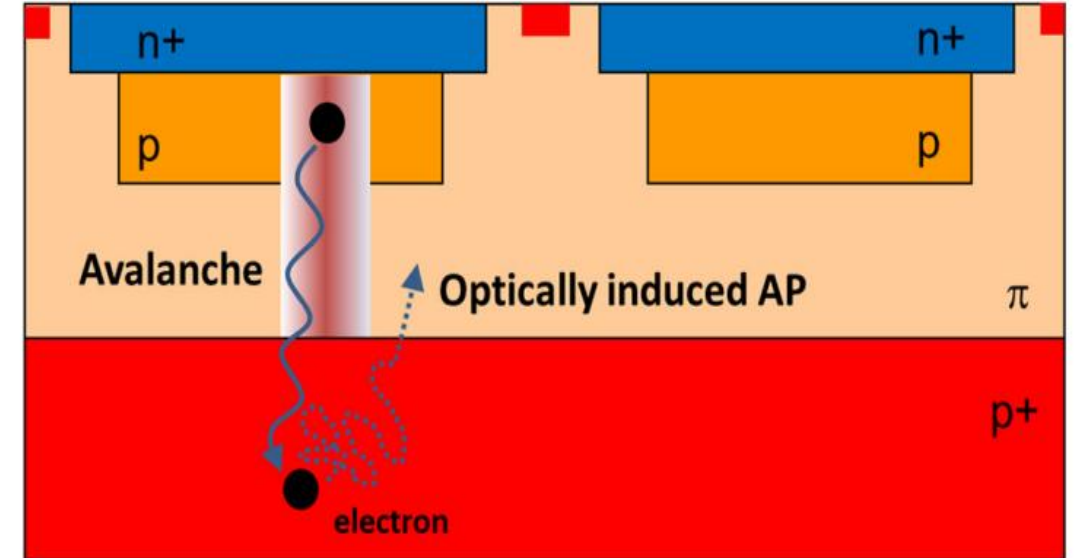
Correlated noise parameters

Cross-talk



- During avalanche, accelerated carriers in the high field region could emit photons
- That photon can initiate a secondary avalanche in a neighbouring microcell.

Afterpulsing



- Carriers get trapped in defects in the silicon.
- Released after a delay which initiate an avalanche in the same microcell.

Figures from Piemonte C and Gola A (2019)

Reverse bias fit model

Pre breakdown fit function :

$$I = q * C_{srh} * W_o * \left\{ \left(\left(1 - \frac{V}{V_{int}} \right)^p - 1 \right) + A \left(\exp \left(\frac{V}{B} \right) - 1 \right) \right\}$$

C_{srh} = Shockley-Read-Hall recombination factor

W_o = Zero bias depletion layer width

V_{int}, \mathbf{p} = CV parameters

A, B = empirical parameters (Otte et al (2017))

Empirical parameters

Reverse bias fit model (contd.)

Post breakdown fit function : involves the contribution of dark noise and correlated noise – afterpulsing and cross-talk

$$I_{post} = C * R_{DN} * V_{ov} * \exp(a * V_{rel}) * \left(1 - \exp\left(-\frac{V_{rel}}{\alpha}\right)\right) * \left\{\left(\frac{1}{1 - P_{CN}(V_{ov}^2)}\right)\right\} + I_o$$

R_{DN} = **Dark noise rate** $V_{ov} = (V - V_{br})$ = Overvoltage , $V_{rel} = \frac{V_{ov}}{V_{br}}$

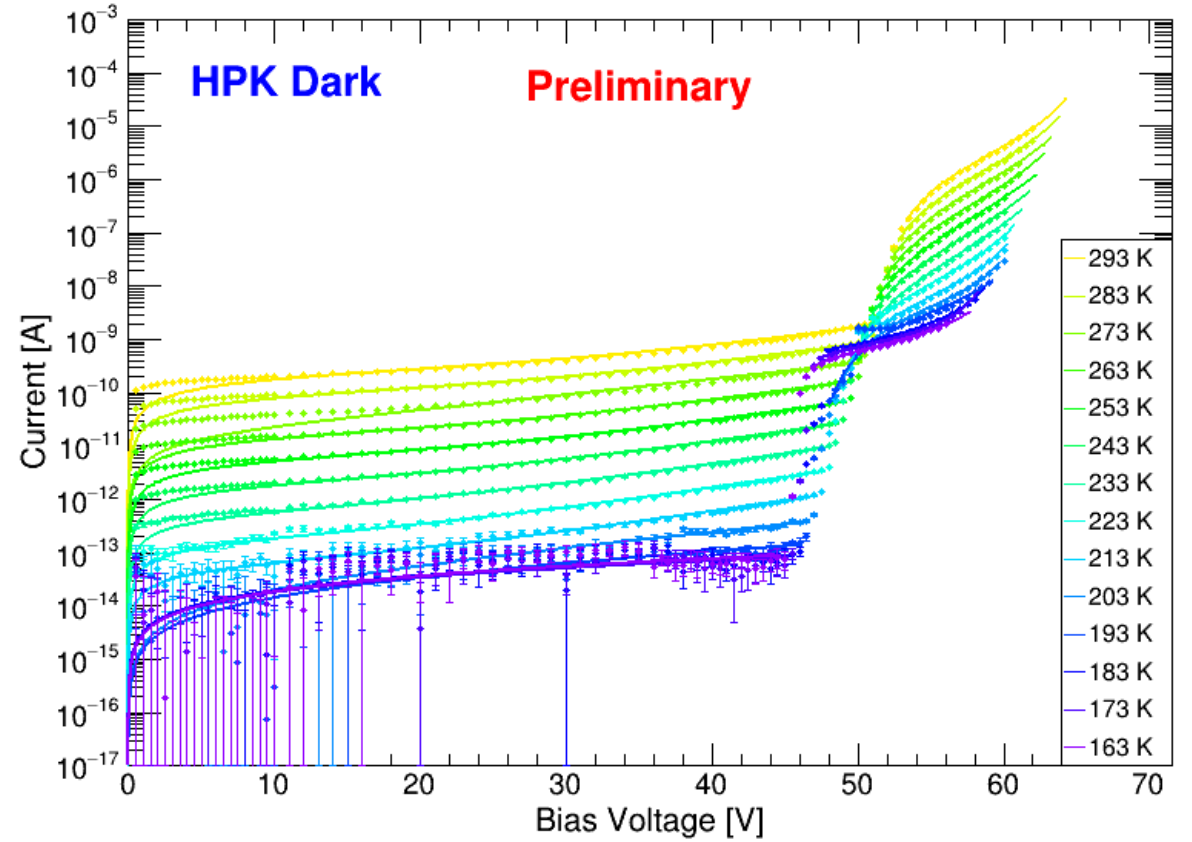
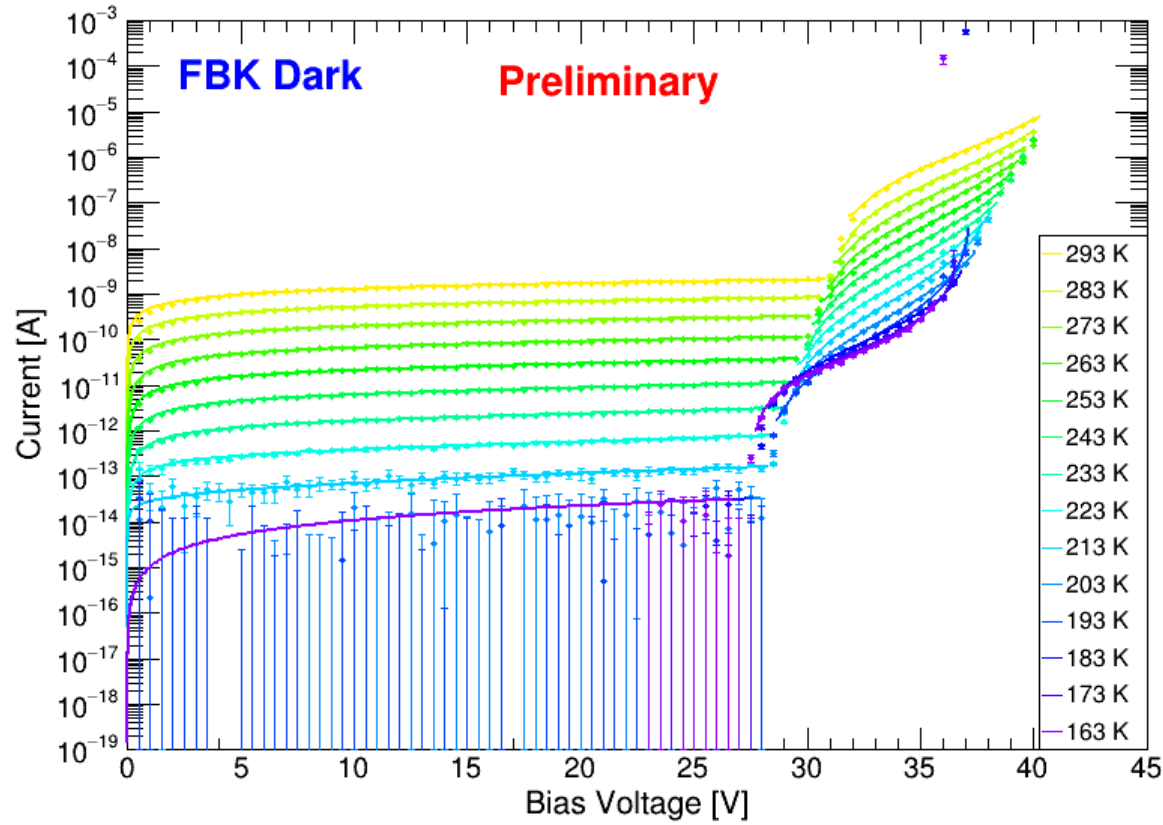
V_{br} = **Breakdown voltage** ; C = Capacitance; I_o = leakage current

P_{CN} = **probability of correlated noise**;

a = empirical parameter accounts for non-linear dependence of voltage on dark noise rate

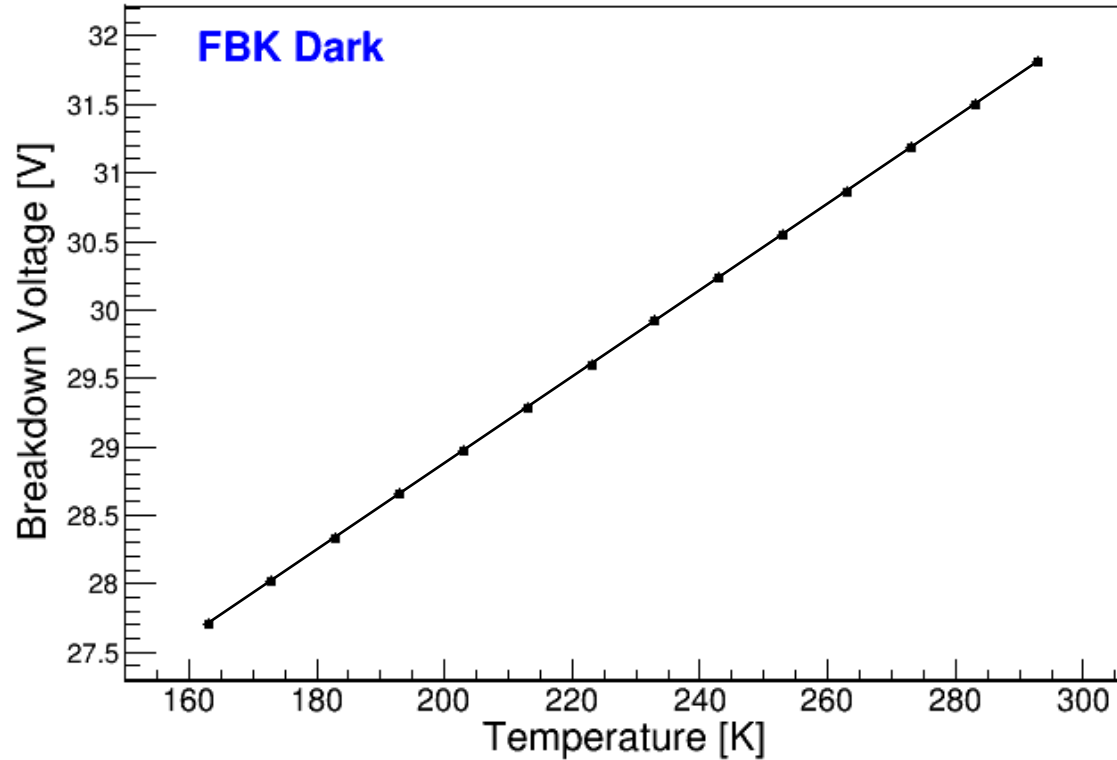
$\left(1 - \exp\left(-\frac{V_{rel}}{\alpha}\right)\right)$ = **triggering probability**

IV fits for 2 devices

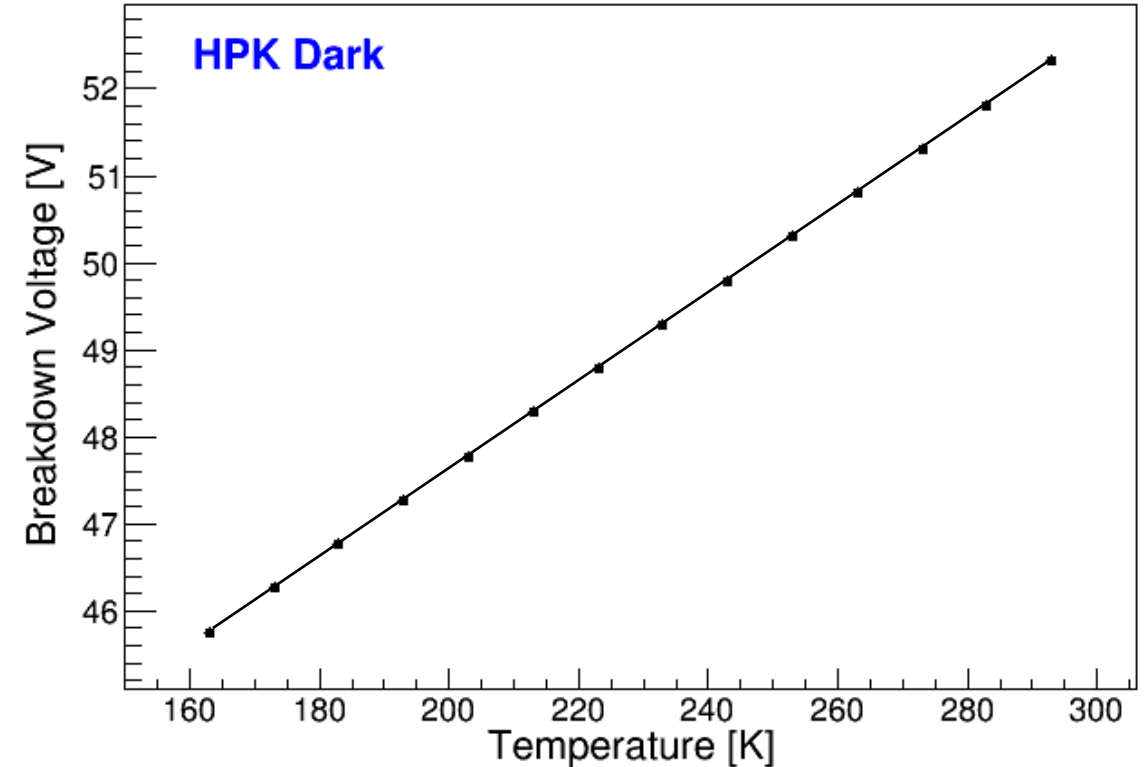


Breakdown Voltage

Preliminary



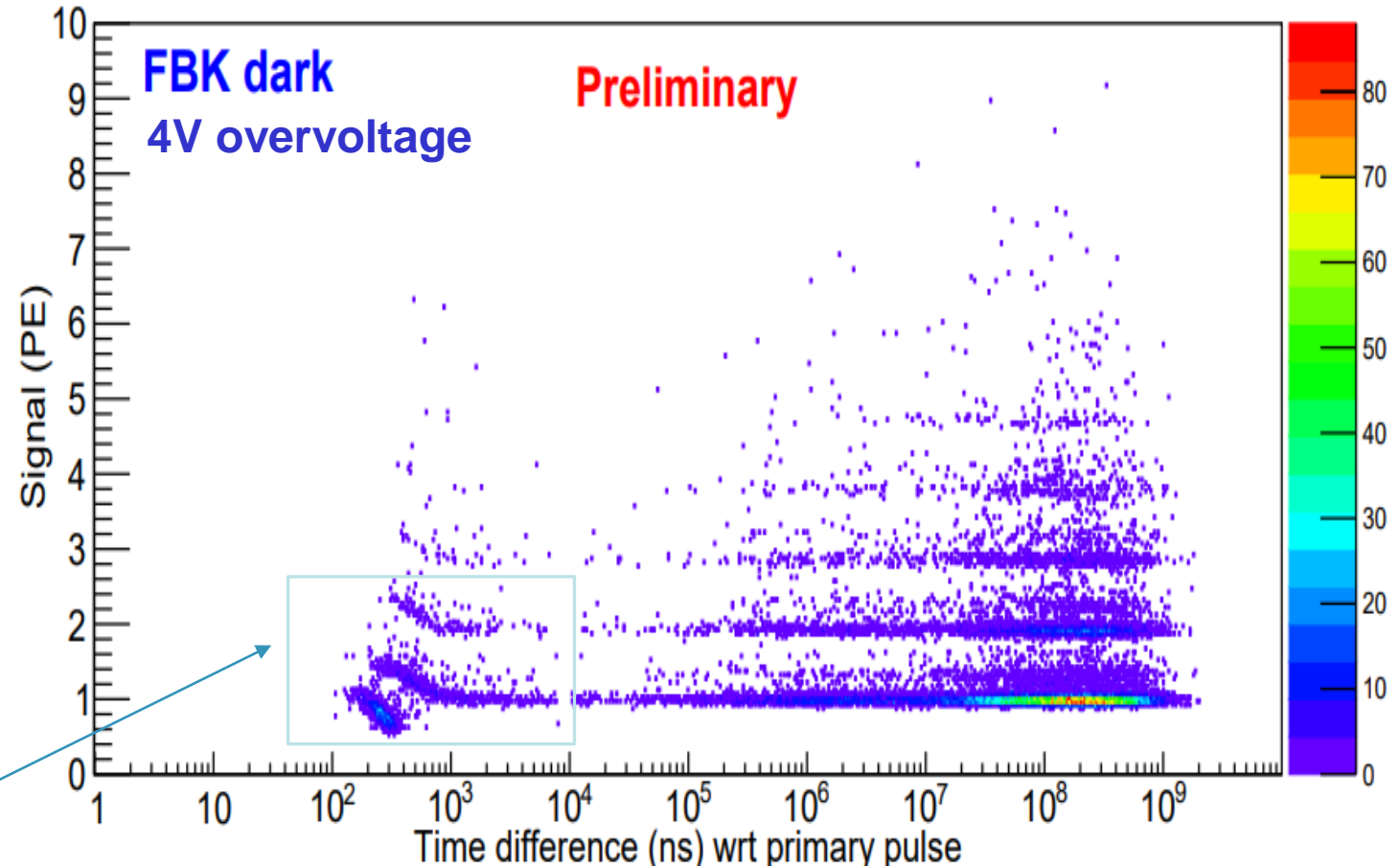
Preliminary



Pulse analysis

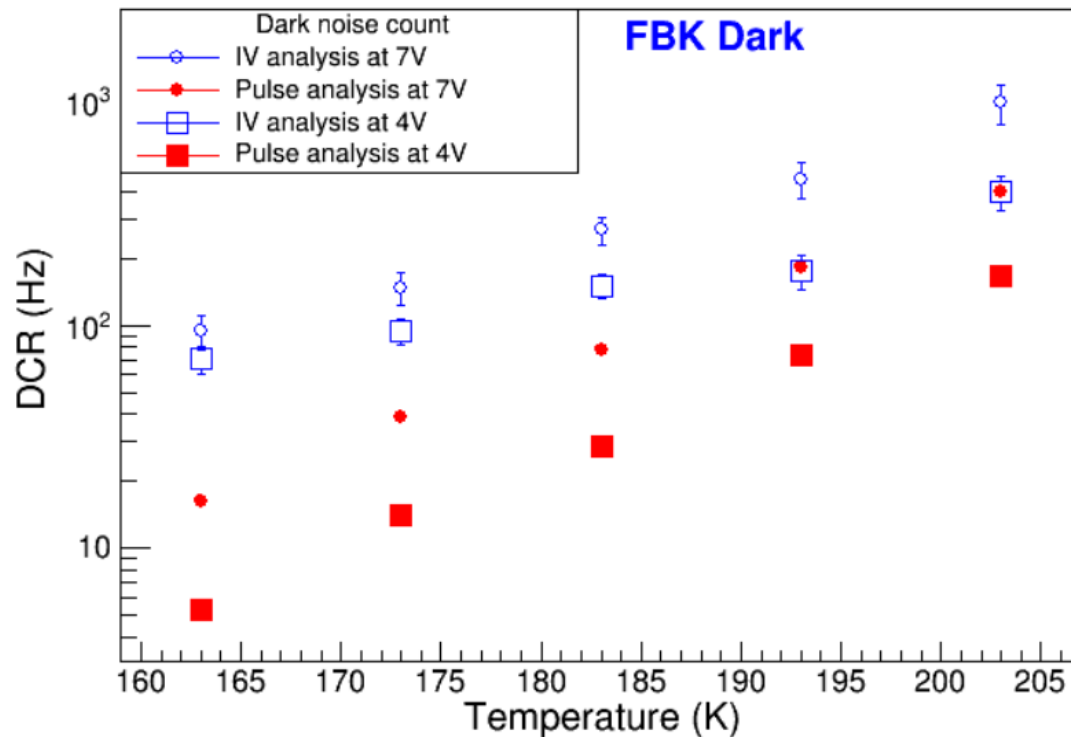
- SiPM pulse data was taken at two overvoltages (4 & 7V) at 0.5PE threshold.
- Primary pulse selection :
 - It should be single PE (0.5 - 1.5PE)
 - It should happen at least 500 μ s later than previous pulse.

Pulse fitting analysis needs improvement for afterpulses and the work is in progress

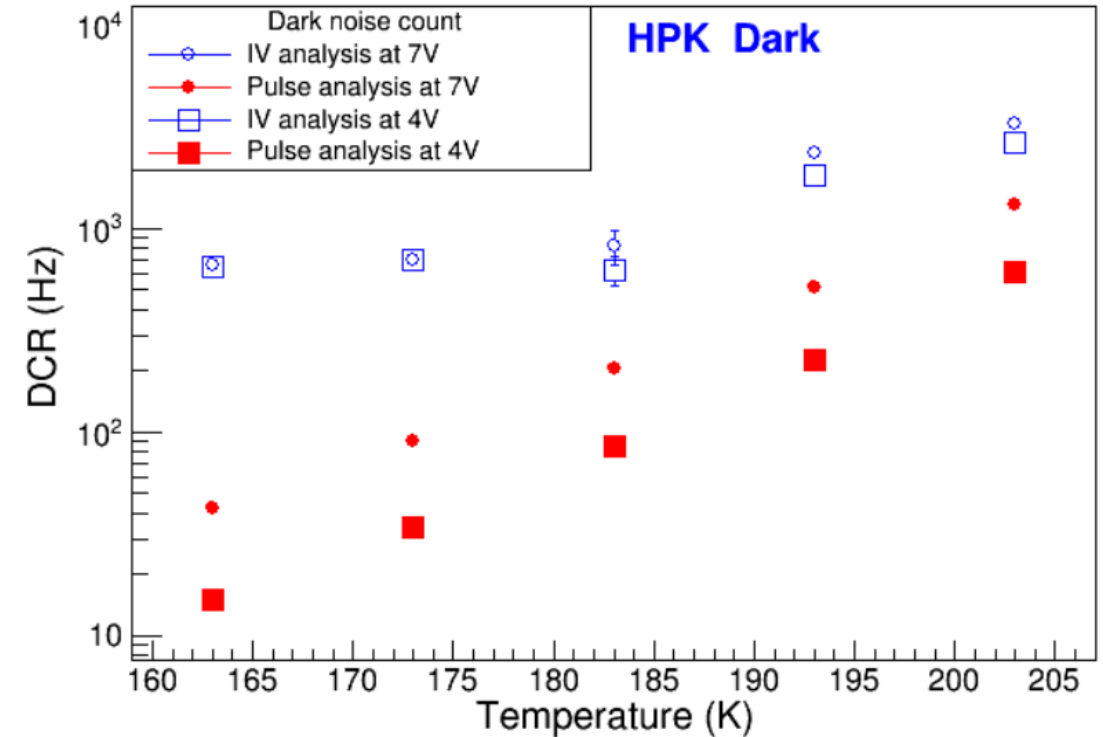


Dark noise rate

Preliminary



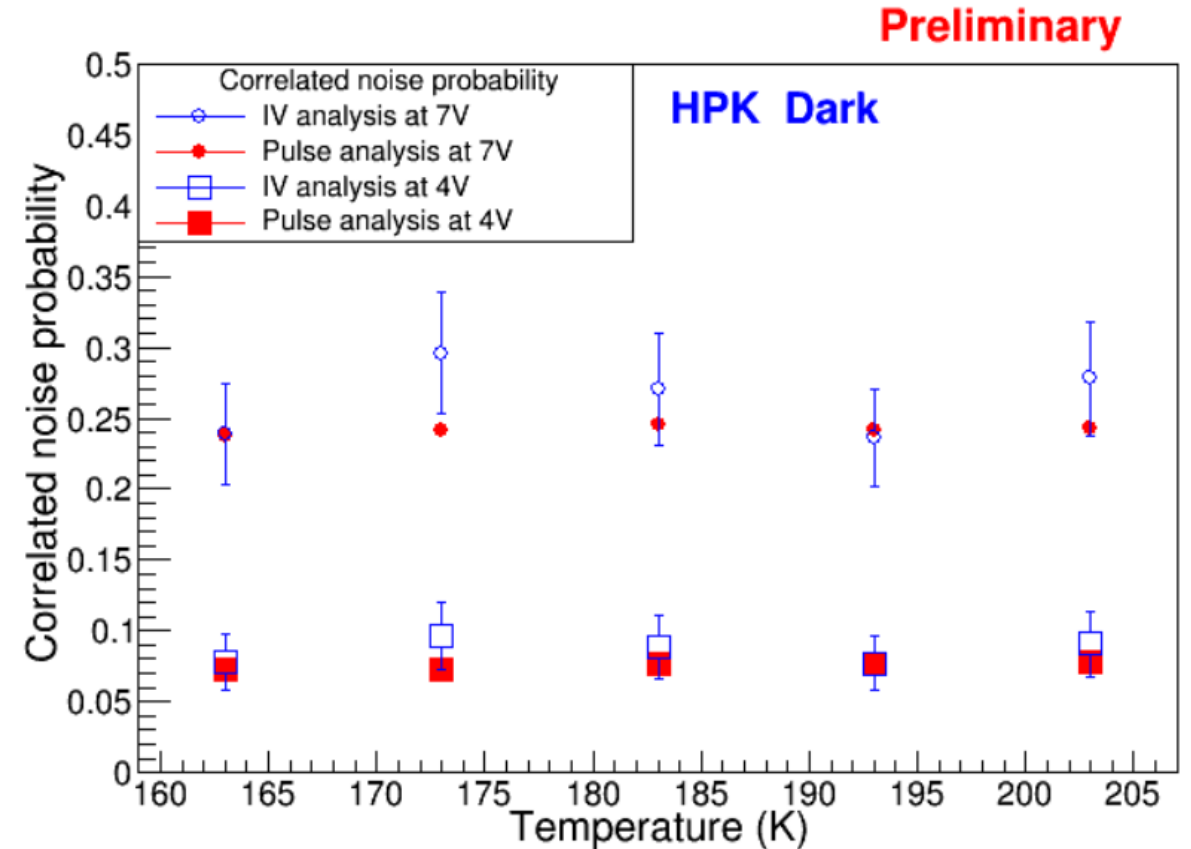
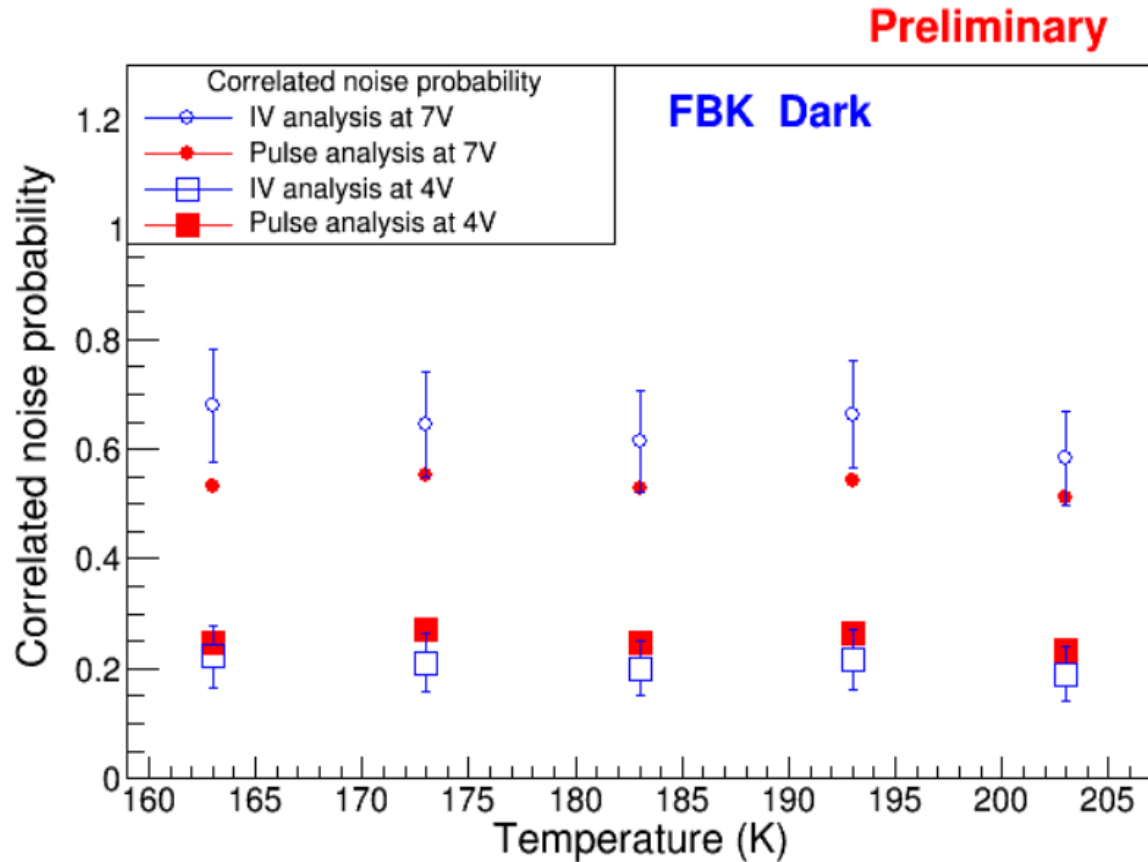
Preliminary



$$\text{Dark count rate} = \frac{N_{>0.5PE}}{\text{Run time (s)}}$$

- Dark count rate (DCR) showed exponential rise with temperature
- It also increases with increase in overvoltage
- IV method overpredicted DCR compared to pulse analysis

Correlated noise probability



$$OC \text{ probability} = \frac{N_{>1.5PE}}{N_{>0.5PE}}$$

- OC probability increases with overvoltage
- Correlated noise seems to be independent of temperature, similar results are indicated by IV analysis as well.

Summary and future plans

- IV characterization and fit model looks promising over a range of temperatures for both FBK and Hamamatsu SiPM devices
- Improve the IV model for dark data
- Extend the fit functions with some additional terms for light data
 - Light data has already been taken and analysis for both IV and pulse data are ongoing
- At TRIUMF, Cryo probe facility will use IV characterization to test thousands of SiPMs for nEXO.